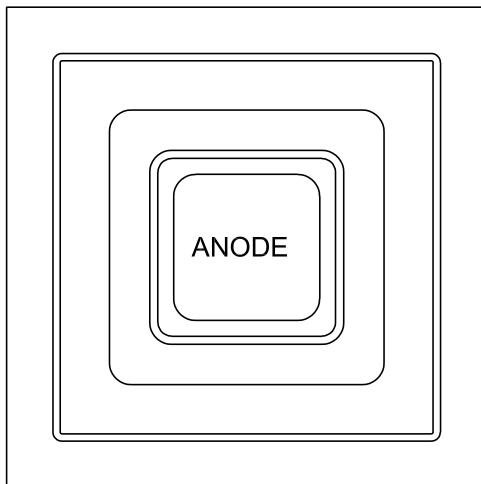


PROCESS DETAILS

| | |
|------------------------|------------------|
| Process | EPITAXIAL PLANAR |
| Die Size | 11 x 11 MILS |
| Die Thickness | 7.1 MILS |
| Anode Bonding pad Area | 3.4 x 3.4 MILS |
| Top Side Metalization | Al - 15,000Å |
| Back Side Metalization | Au - 18,000Å |

GEOMETRY



BACKSIDE: CATHODE R0

GROSS DIE PER 4 INCH WAFER

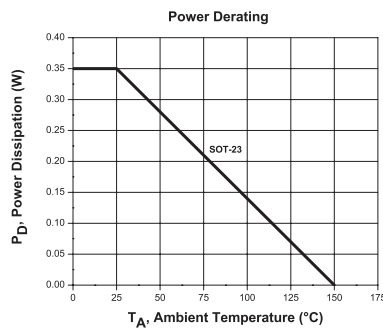
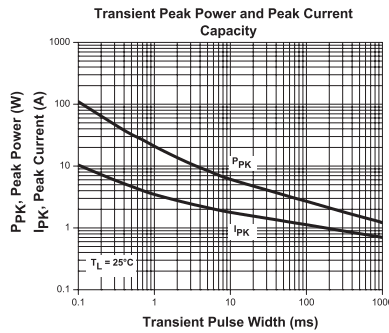
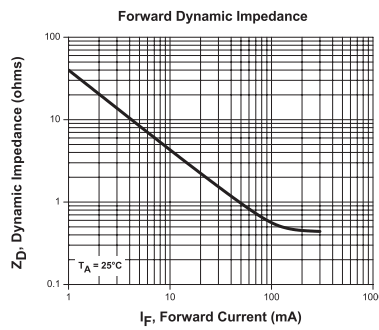
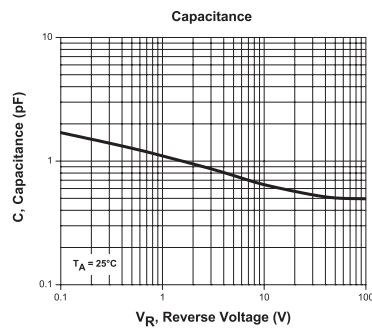
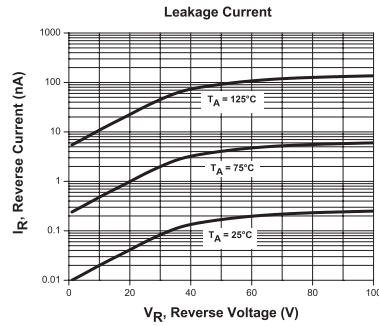
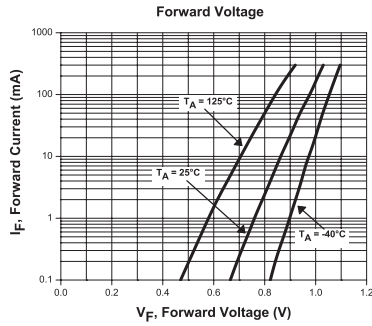
94,130

PRINCIPAL DEVICE TYPES

CMPD6001 Series
CMOD6001
CMLD6001
CMLD6001DO
CMDD6001

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